

Ni Sputtering Film using Sputter#3 (8-18-2016)

Condition: 3 mT, 200 W (389 V), Ar flow-rate=25 sccm, 44mm/4 (tilt angle), and Sputtering Time=480 seconds.

Result:

- 1) Average film thickness measured by SEM=75.1 nm.
- 2) Ni Sputtering Rate=9.4 nm/min.

Figure 1 Profile of Ni film.

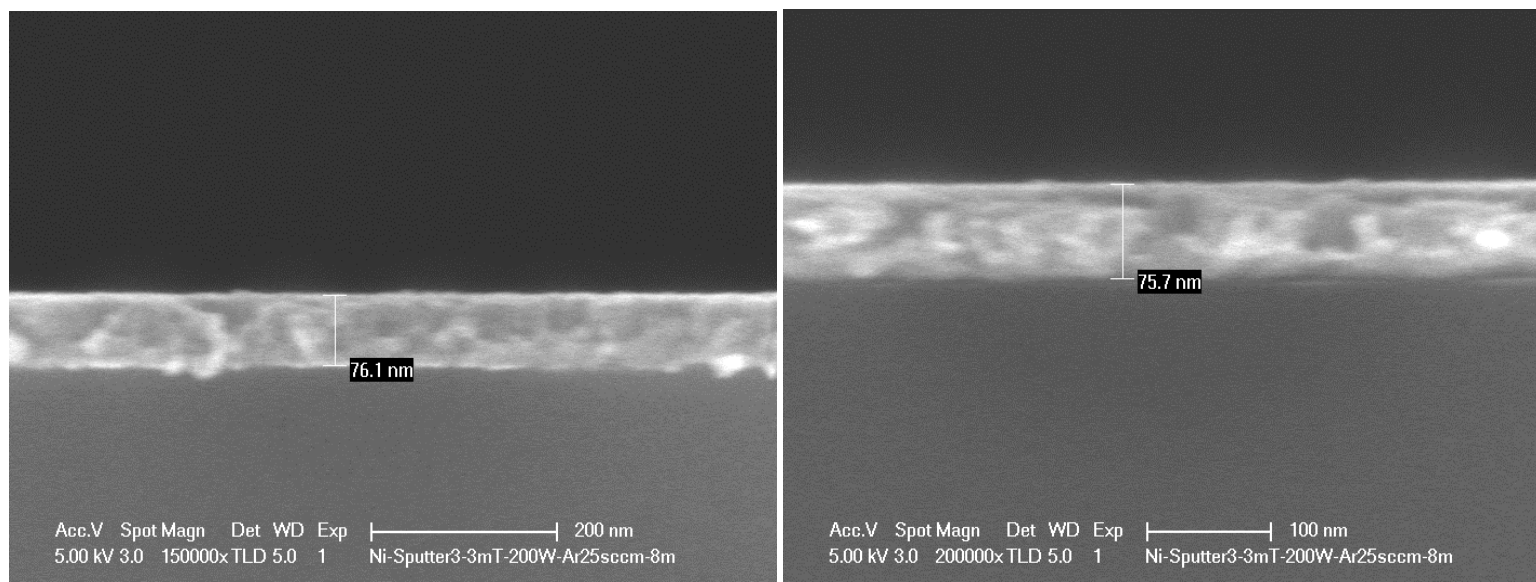


Figure 2 Film Thickness measured by Ellipsometer.

